

## (57) Abstract

The present invention concerns a method and an apparatus for feeding a gas phase reactant from a reactant source into a gas phase reaction chamber. In the method a reactant which is  
5 a liquid or solid at ambient temperature is vaporised from the reactant source at a vaporising temperature; and the vaporised reactant is fed into the reaction chamber. According to the invention the reactant source and the reaction chamber are located in separate vessels which can be individually evacuated. By means of the invention it becomes possible to change and load new reactant chemical without breaking the vacuum  
10 of the reaction chamber.